## ABSTRACT

This specification discloses an exposure mask, a method of designing and 5 manufacturing an exposure mask, an exposure method and apparatus, a pattern forming method, and a device manufacturing method. Specifically, the exposure mask is adapted to expose an image forming layer provided on a substrate, by use of 10 near field light leaking from adjoining openings formed in a light blocking member, wherein the light blocking film has an opening interval that is determined so that an electric field distribution at the image forming layer side of . 15 the opening to be defined as exposure light is projected on the light blocking member has a correlation with an eccentric model of electric field distribution as determined by a linewidth and a height of a pattern to be produced.